

The VDE/VDI-Society Microelectronics, Micro- and Precision Engineering (GMM) in cooperation with BACUS, PMJ, SEMI-Europe, SPIE, and UBC Microelectronics are pleased to present the

24th European Mask and Lithography Conference, EMLC2008

**Dresden, Germany
January 21st - January 24th, 2008
www.emlc2008.com**

The focus of this three-day conference is "state-of-the-art" for the development of mask technologies such as lithography, data processing, RET, OPC, resist, metrology, and inspection.

This conference has annually brought together scientists, researchers, engineers and developers from around the world to present papers at the forefront of the photomask manufacturing and research. It provides a place where mask makers, mask users and their tool suppliers have the opportunity to become acquainted with new developments and results.

Technical Exhibition

There will be a technical exhibition on Tuesday and Wednesday of the conference week. Presentation tables and pin boards will be available. For the Technical Exhibition registration please use the attached registration form and send it to the conference chairperson.

Conference Chairperson and Exhibition Organization

UBC Microelectronics
Dr. Uwe Behringer
Auf den Beeten 5
72119 Ammerbuch, Germany
Phone: ++49-171-455 3196
Fax: ++49-7073-50216
E-Mail: uwe.behringer.ubc@t-online.de

Abstract Information

The quality of the abstracts will form the basis for selection of papers for the conference. The abstracts will be peer reviewed according to the following criteria:

- Originality of work
- Specific results that have been obtained
- Potential impact and interest to the attendees.

Therefore, we highly recommend that your abstract contain enough detail to clearly describe the content of the presentation. The abstracts should include at least one page of text (minimum of 500 words) and the use of figures is encouraged. Commercial papers, papers with no new research/development content, and papers where significant information will be omitted, will not be accepted.

With the submission of your abstract you agree to submit a manuscript.

Deadline for Abstracts: August 17th, 2007

All accepted abstracts will be printed, bound, and handed out to the participants of the conference. You are strongly encouraged to submit abstracts using the provided guidelines at

www.emlc2008.com

Information for Authors

Authors will be notified of the acceptance of their submissions by **October 12th**; further manuscript format and layout instructions will be provided at that time.

Manuscripts for the Proceedings

An original of the manuscript should be sent in by **January 14th, 2008** at the latest.

All manuscripts will be subject to a critical peer review before they can be accepted for publication in the SPIE/VDE publication and in the SPIE Digital Library. Please note: Late submissions may not be printed in the SPIE/VDE publication or be included in the SPIE Digital Library.

Conference Topics

Presentations are being solicited on the following topic areas:

Mask Manufacturing:

- Pattern Generation and Data Preparation
- Photomask- Processes and Materials
- Mask Process Yield
- Photomasks with RET and OPC; PSM
- Mask for NGL: E-Beam, EUV; NIL etc.
- Metrology Tools and Technologies
- Defect Inspection- and Repair Tools
- Cleaning and Pelliclization

Mask Business

- Mask Business and Management
- Direct Write / Maskless Technologies

Other Mask Topics:

- Mask Cost and Mask Development Strategy
- Future Mask Demand

Lithography and Mask Applications

- RET, OPC, Double Exposure, MEEF
- Resist
- Mask Defect Printability
- Optical Materials
- Immersion Lithography
- Immersion Defectivity
- Alternate Immersion Fluids
-

Emerging Mask and Lithography Technologies:

- 157nm
- EUV Mask Material
- EUV Mask Infrastructure
- NIL
- Double Exposure

Mask and Lithography Equipment

Organizers

VDE/VDI-Society Microelectronics, Micro- and Precision Engineering (GMM)
Dr.-Ing. Ronald Schnabel
Stresemannallee 15
60596 Frankfurt/Main, Germany
Phone: ++49-69-6308-330
Fax: ++49-69-6308-9828
E-Mail: gmm@vde.com

In cooperation with:
UBC Microelectronics
Dr. Uwe Behringer

Venue

Hilton Hotel in the Center of Dresden



Dresden at the river Elbe



Cover picture: Courtesy of Toppan Photomasks

The International Program Committee of the 24th European Mask and Lithography Conference, EMLC 2008

Conference Chair: Dr. U. Behringer,
UBC Microelectronics, Ammerbuch,
Germany
Program Chairs: Dr. W. Maurer,
Infineon Technologies, Munich,
Germany
Mr. J. Waelpoel,
ASML, Veldhoven, The Netherlands

Dr. M. Arnz, Carl Zeiss SMT AG, Oberkochen, Germany
Mr. P. Chen, Taiwan Mask Corp., Hsinchu, Taiwan
Mr. C. Gale, Applied Materials GmbH, Dresden, Germany
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Italy
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Mrs. I. A. Stolberg, Vistec Electron Beam GmbH, Jena,
Germany
Dr. S. Tedesco, CEA-LETI, Grenoble, France
Dr. M. Tissier, Toppan Photomasks S.A., Rousset, France
Mr. G. Unger, Qimonda Dresden GmbH & Co. OHG,
Germany
Mr. J. Whittey, Vistec Semiconductor Systems, Oakdale,
CA, USA
Mr. H. Wolf, Photronics MZD GmbH, Dresden, Germany
Mr. L. Zurbrick, KLA-Tencor Corp., San Jose, CA, USA

GMM VDE/VDI-GESELLSCHAFT
MIKROELEKTRONIK,
MIKRO- UND FEINWERKTECHNIK



Call for Papers

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